



IFW

Patent Application No. 10/687,424  
Customer No. 42717

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Jhon Jhy Liaw	§	Docket No.:	24061.39 / 2003-0030
Serial No.:	10/687,424	§	Examiner:	Kin Chan Chen
Filing Date:	October 16, 2003	§	Art Unit:	1765
For:	Process Integration of SOI FETs With Active Layer Spacer	§	Conf. No.:	8019

RESPONSE UNDER EX PARTE QUAYLE ACTION

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed on May 23, 2005, please enter the amendment herein to correct defects as to formal matters.

**Amendments to the Claims** are reflected in the listing of claims, which begins on page 2 of this paper.

**Remarks** begin on page 4 of this paper.